

	Hits	Search Text	DBs
1	8	(("6191397") or ("6603101") or ("6550990") or ("6483083") or ("6495807") or ("6441351") or ("6376139") or ("6333493")).PN.	USPAT; US-PGPUB
2	40	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4) same support same (wafer or substrate)) and (((partition with member) or electrode or ((charg\$3 or ceramic) near2 plate)) same (permeable or permeat\$3 or porous)) and ((air or gas or nitrogen) with (purge or stream or port))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	3	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4) same support same (wafer or substrate) same ((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate)) same (permeable or permeat\$3 or porous)) and ((air or gas or nitrogen) with (purge or stream or port))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	2	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4) same support same (wafer or substrate)) and ((wafer or substrate or workpiece) same (resist or photoresist or (acid with generat\$4) or (acid with liberat\$4) or (chemical\$2 near2 amplif\$4 near3 resist)) same ((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate)) same (permeable or permeat\$3 or porous)) and ((air or gas or nitrogen) with (purge or stream or port))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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5	21	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4) same support same (wafer or substrate)) and ((wafer or substrate or workpiece) same (resist or photoresist or (acid with generat\$4) or (acid with liberat\$4) or (chemical\$2 near2 amplif\$4 near3 resist))) and (((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate)) same (permeable or permeat\$3 or porous)) and ((air or gas or nitrogen) with (purge or stream or port))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	68	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4) same support same (wafer or substrate)) and ((wafer or substrate or workpiece) same (resist or photoresist or (acid with generat\$4) or (acid with liberat\$4) or (chemical\$2 near2 amplif\$4 near3 resist)) same ((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate))) and ((air or gas or nitrogen) with (purge or stream or port or inlet))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
7	2	((plate or holder or (support near3 surface)) same (heat\$4 or bak\$4 or post\$2bak\$3 or post\$2expos\$4bak\$3 or PEB) same support same (wafer or substrate) same (resist or photoresist)) and (((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate) or (electric with field)) same (permeable or permeat\$3 or porous) same ((air or gas or nitrogen) with (purge or stream or port))) and (system or apparatus or chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
8	8	((("6191397") or ("6603101") or ("6550990") or ("6483083") or ("6495807") or ("6441351") or ("6376139") or ("6333493")).PN.	USPAT; US-PGPUB
9	0	("L22and(resistorphotoresist)").P N.	USPAT; US-PGPUB

	Hit s	Search Text	DBs
10	2	((plate or holder or (support near3 surface)) same (heat\$4 or bak\$4 or post\$2bak\$3 or post\$2expos\$4bak\$3 or PEB) same support same (wafer or substrate) same (resist or photoresist)) and (((partition with member) or electrode or ((charg\$3 or ceramic or absorption) near2 plate) or (electric with field) or (temperature with control\$5)) same (permeable or permeat\$3 or porous) same ((air or gas or nitrogen) with (purge or stream or port))) and (system or apparatus or chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
11	1	("20020123011").PN.	USPAT; US-PGPUB
12	1	("6644964").PN.	USPAT; US-PGPUB
13	8	(heat\$4 with (apparatus or system)) and ((plate or surface or holder) same (heat\$4 or bak\$4 or thermal\$3) same (support or wafer or substrate)) and ((wafer or substrate or workpiece) same (resist or photoresist or coating or film) same ((partition with member) or ((porous or permea\$4 or adsor\$4) near4 (separator or electrode or member or plate)))) and ((air or gas or nitrogen) with (purge or stream or port or inlet)) and ((system or chamber) same (first near3 (exhaust\$4 or open\$4 or inlet or vent or outlet)) same (second near3 (open\$4 or vent or outlet or inlet or exhaust)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB